

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (canceled).
2. (canceled).
3. (currently amended): A method for removing an uncured photosensitive composition film containing a pigment remaining at the periphery, edges, or back of a substrate or an uncured photosensitive composition containing a pigment deposited at the surface of system members or equipment, comprising removing the uncured photosensitive composition film or uncured photosensitive composition with a photosensitive composition remover~~used for removal of an uncured photosensitive composition, which remover consists~~ consisting essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,
wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,
~~wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;~~
wherein the other solvent other than aprotic polar solvents is at least one selected from the group consisting of glycol ethers excluding dipropylene glycol monomethyl ether, glycol ether carboxylates, carboxylic acid esters excluding ethyl acetate and amyl acetate, hydroxycarboxylic acid esters, ketones, alkoxycarboxylic acids esters, and cyclic ethers.
4. (canceled).

5. (canceled).
6. (currently amended): ~~A photosensitive composition remover~~A method as set forth in claim 3, wherein 30 to 60 percent by mass of propylene glycol monomethyl ether is present in the remover.
7. (canceled).
8. (canceled).
9. (canceled).
10. (canceled).
11. (canceled).
12. (currently amended): ~~A photosensitive composition remover~~A method as set forth in claim 3, used for removal of an acrylic photosensitive composition containing a pigment.
13. (canceled).
14. (currently amended): ~~A photosensitive composition remover~~A method as set forth in claim 3, wherein the remover consists of solvents.
15. (canceled).
16. (currently amended): ~~A photosensitive composition remover~~A method as set forth in claim 3, wherein the other solvent other than aprotic polar solvents is two or more of propylene glycol monomethyl ether, propylene glycol monomethyl ether acetate, butyl acetate, ethyl 3-ethoxypropionate, methyl 3-methoxypropionate, and cyclohexanone.
17. (canceled).
18. (currently amended): ~~A photosensitive composition remover~~A method as set forth in claim 6, wherein the other solvent other than aprotic polar solvents other than propylene glycol monomethyl ether is at least one selected from the group consisting of propylene glycol

monomethyl ether acetate, butyl acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate.

19. (currently amended): A method for removing an uncured photosensitive composition film containing a pigment remaining at the periphery, edges, or back of a substrate or an uncured photosensitive composition containing a pigment deposited at the surface of system members or equipment, comprising removing the uncured photosensitive composition film or uncured photosensitive composition with a photosensitive composition remover-used for removal of an uncured photosensitive composition, which remover consists consisting essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

~~wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;~~

wherein the other solvent other than aprotic polar solvents comprises a glycol monoalkyl ether and at least one selected from the group consisting of glycol ether carboxylates, carboxylic acid esters, hydroxycarboxylic acid esters, ketones, alkoxycarboxylic acids esters, and cyclic ethers.

20. (new): A method for removing an uncured photosensitive composition film containing a pigment remaining at the periphery, edges, or back of a substrate or an uncured photosensitive composition containing a pigment deposited at the surface of system members or equipment in a process for forming a photosensitive composition film on a glass substrate or semiconductor wafer, comprising removing the uncured photosensitive composition film or

uncured photosensitive composition with a photosensitive composition remover comprising 1 to 80 percent by mass of at least one type of aromatic hydrocarbon having 9 carbon atoms or more within the molecule.

21. (new): A method as set forth in claim 3, wherein the aromatic hydrocarbon comprises a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, or a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

22. (new): A method as set forth in claim 20, wherein the aromatic hydrocarbon having 9 carbon atoms or more within the molecule is an alkylbenzene having a boiling point of 150 to 250°C.

23. (new): A method as set forth in claim 20, wherein the photosensitive composition remover has a composition selected from the group consisting of

a composition of 20 to 80 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 20 to 80 percent by mass of one or more aprotic polar solvent(s) when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more aprotic polar solvent(s);

a composition of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more other solvent(s) other than aprotic polar solvents; and

a composition of 20 to 30 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, 1 to 20 percent by mass of one or more

aprotic polar solvent(s), and 55 to 70 percent by mass of one or more other solvent(s) other than aprotic polar solvents when the remover comprises one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, one or more aprotic polar solvent(s), and one or more other solvent(s) other than aprotic polar solvents.

24. (new): A method as set forth in claim 20, wherein the photosensitive composition remover has a composition selected from the group consisting of

a composition of 20 to 40 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 60 to 80 percent by mass of one or more aprotic polar solvent(s) when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more aprotic polar solvent(s);

a composition of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents, wherein the remover comprises 30 to 60 percent by mass of propylene glycol monomethyl ether, when the remover consists essentially of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and one or more other solvent(s) other than aprotic polar solvents; and

a composition of 20 to 30 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, 3 to 20 percent by mass of one or more aprotic polar solvent(s), and 55 to 70 percent by mass of one or more other solvent(s) other than aprotic polar solvents, the aprotic polar solvent(s) being at least one selected from the group consisting of N,N-dimethylformamide and N,N-dimethylacetamide, and the other solvent(s) other than aprotic polar solvents being at least one selected from the group consisting of

propylene glycol monomethyl ether acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate, when the remover comprises one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, one or more aprotic polar solvent(s), and one or more other solvent(s) other than aprotic polar solvents.

25. (new): A method as set forth in claim 20, wherein the photosensitive composition remover comprises 20 to 40 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 60 to 80 percent by mass of one or more aprotic polar solvent(s).

26. (new): A method as set forth in claim 20, wherein the photosensitive composition remover comprises 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents, wherein the remover comprises 30 to 60 percent by mass of propylene glycol monomethyl ether.

27. (new): A method as set forth in claim 20, wherein the photosensitive composition remover comprises 20 to 30 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule, 3 to 20 percent by mass of one or more aprotic polar solvent(s), and 55 to 70 percent by mass of one or more other solvent(s) other than aprotic polar solvents, wherein the aprotic polar solvent is at least one selected from the group consisting of N,N-dimethylformamide and N,N-dimethylacetamide, and the other solvent other than aprotic polar solvents is at least one selected from the group consisting of propylene glycol monomethyl ether acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate.

28. (new): A method as set forth in claim 23, wherein the aprotic polar solvent is at least one selected from the group consisting of chain amide compounds, cyclic amide compounds, sulfur compounds, and cyclic esters.

29. (new): A method as set forth in claim 23, wherein the aprotic polar solvent is at least one selected from the group consisting of formamide, N-methylformamide, N,N-dimethylformamide, N-ethylformamide, N,N-diethylformamide, N,N-dimethylacetamide, tetramethyl urea, N-methyl-2-pyrrolidone, N-methylimidazolidinone, dimethyl sulfoxide, sulfolane, and γ -butyrolactone.

30. (new): A method as set forth in claim 26, wherein the other solvent other than aprotic polar solvents is at least one selected from the group consisting of glycol ethers, glycol ether carboxylates, carboxylic acid esters, hydroxycarboxylic acid esters, ketones, alcohols, alkoxycarboxylic acids esters, and cyclic ethers.

31. (new): A method as set forth in claim 20, wherein the photosensitive composition is an acrylic-type photosensitive composition containing a pigment.

32. (new): A method as set forth in claim 19, wherein the aromatic hydrocarbon comprises a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, or a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

33. (new): A method as set forth in claim 20, wherein the aromatic hydrocarbon comprises a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, or a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

34. (new): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover consists essentially of 10 to 20 percent by mass of

one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents is two or more of propylene glycol monomethyl ether, propylene glycol monomethyl ether acetate, butyl acetate, ethyl 3-ethoxypropionate, methyl 3-methoxypropionate, and cyclohexanone;

wherein 30 to 60 percent by mass of propylene glycol monomethyl ether is present in the remover.